



DuPont Photomasks, Inc.

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NEWS RELEASE

DuPont Photomasks Receives Spansion's 'Spotlight Award' for Yield Improvements on Flash Memory

ROUND ROCK, Texas — March 24, 2005— DuPont Photomasks, Inc. (NASDAQ: DPMI) today said it has received a "Spotlight Award" from flash memory device maker Spansion LLC for helping Spansion's FAB25 in Austin, Texas, enhance wafer yield. Spansion's award recognizes DuPont Photomasks' role in a joint-development project (JDP) aimed at boosting yield by targeting improvement of layer-to-layer registration when chip designs are etched on wafers. Spansion, formerly known as FASL LLC, is the flash memory subsidiary of AMD and Fujitsu Limited.

Layer-to-layer registration refers to how closely the images produced by individual photomasks in a set align with one another as they are used to print various layers of the semiconductor. Improving layer-to-layer registration improves memory devices' reliability, programming performance and their ability to remain charged. Working with a team of lithography and metrology engineers from Spansion, DuPont Photomasks was able to provide products with registration tolerances below 15nm using an ALTA® 4300 laser-based pattern generation system.

"By optimizing our proprietary photomask processes, we were able to achieve a 50 percent improvement in tolerance," said Jim Northup, chief operating officer, DuPont Photomasks. "This continuing JDP shows clearly how exchanging ideas between customers and suppliers can improve yields, reduce costs and accelerate technology. DuPont Photomasks is committed to this kind of collaboration with customers and other partners to break through the technological barriers of deep submicron design rules."

"These improvements in tolerance translate into better device performance, which helps us, our OEM customers and, ultimately, end users of the products that our flash memory devices go into," said Greg Goodwin, strategic technology manager for Spansion LLC. "This Spotlight Award recognizes DuPont Photomasks' commitment to help improve Spansion's die yield per wafer and the reliability of our flash devices. These gains increase Spansion's competitiveness and improve our return on investment."

In December 2004, DuPont Photomasks and Applied Materials, Inc. jointly announced a separate JDP to bring an Applied ALTA® 4700 laser-based pattern generator into production this quarter at DuPont Photomasks' advanced production facility in Round Rock. The new system, whose enhanced capabilities include higher NA lens and improved registration performance than the ALTA 4300, will support volume manufacturing of 90nm and 65nm

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critical photomask layers. It is expected to further strengthen DuPont Photomasks' leadership role in the use of advanced laser-based pattern generation systems and provide customer partners such as Spansion with early access to the most advanced photomask technologies available.

About Spansion LLC

Spansion™ Flash memory products encompass a broad spectrum of densities and features to support a wide range of markets. Spansion Flash memory customers represent leaders in the wireless, cellular, automotive, networking, telecommunications and consumer electronics markets. There are a variety of Spansion Flash memory products, such as devices based on the innovative MirrorBit™ technology; the award-winning simultaneous read-write (SRW) product family; super low-voltage 1.8-volt Flash memory devices; and burst- and page-mode devices. Information about Spansion Flash memory solutions is available at www.spansion.com/overview.

Spansion was formed by the integration of AMD's and Fujitsu's Flash memory operations in 2003. It is the largest NOR Flash memory company in the world. Spansion Flash memory solutions are available worldwide from AMD (NYSE:AMD) and Fujitsu (TSE:6702).

About DuPont Photomasks, Inc.

DuPont Photomasks, Inc. is a leading global provider of microimaging solutions. The Company develops and produces advanced photomasks, a key enabling technology used in the manufacture of semiconductor and other microelectronic devices. Headquartered in Round Rock, Texas, DuPont Photomasks operates a global network of manufacturing facilities serving semiconductor makers and other electronics producers around the world. DuPont Photomasks posted worldwide revenues of \$354 million in fiscal 2004. Information about the Company can be found at www.photomask.com.

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Forward-Looking Statements

Certain statements contained in this document that are not historical facts, are "forward-looking statements," as that term is defined in Section 27A of the Securities Act of 1933 and Section 21E of the Securities Exchange Act of 1934, that involve a number of risks and uncertainties. Such forward-looking statements may concern growth and future operating results, forecasts, projections, pricing pressures, potential acquisitions and joint ventures, new manufacturing facilities, capital expenditures, the global economic climate, new products and product enhancements, the future importance of photomask technology, the demand for products, competitive factors, research and development activities and expenditures, strategic relationships with third parties, liquidity, financing, and the Company's strategy. Such forward-looking statements are based upon management's current plans, expectations, estimates and assumptions and are subject to a number of risks and uncertainties. Actual events or results may differ materially from those described in this press

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release due to a number of risks and uncertainties. Additional risk factors affecting our business may include relationships with and dependence on the semiconductor industry, fluctuations in quarterly and annual earnings, operating in a capital intensive industry, significant fixed costs, rapid technological change, competition, significant international operations, world-wide market volatility, manufacturing risks, fluctuation of income tax rates, concentration of customers, dependence on suppliers, dependence on management and technical personnel, volatility of market prices, potential acquisitions or dispositions technology challenges in the manufacture of advanced photomasks, intellectual property, changes in governmental laws and regulations, and the potential effect of shares eligible for future sales and registration rights. More information about potential factors that could affect DuPont Photomasks' business and financial results are more fully discussed under the caption "Risk Factors" in the Company's Form 10-K filed with the Securities and Exchange Commission (The "SEC") dated September 9, 2004 and the Company's quarterly report on Form 10-Q dated February 8, 2005, each of which is on file with the SEC and available at the SEC's website at www.sec.gov. The forward-looking statements are made as of the release date hereof and DuPont Photomasks disclaims any intention or obligation to update or revise any forward-looking statements or to update the reasons why the actual results could differ materially from those projected in the forward-looking statements, whether as a result of new information, future events or otherwise.